Notice of Allowability	Application No.	Applicant(s)
	10/721,920	AHN ET AL.
	Examiner	Art Unit
	Michael Trinh	2822
The MAILING DATE of this communication appea. All claims being allowable, PROSECUTION ON THE MERITS IS (herewith (or previously mailed), a Notice of Allowance (PTOL-85) on Notice of the Office or upon petition by the applicant. See 37 CFR 1.313 on the Office or upon petition by the applicant. See 37 CFR 1.313 on the Office of the Office of the Office of the India (PTOL-152) on Notice of the India (PTOL-152) on Notice of International Bureau (PCT Rule 17.2(a)). * Certified copies of the certified copies of the priority documents have a copies of the Copies of the Priority on Notice of International Bureau (PCT Rule 17.2(a)). * Certified copies not received: Applicant has THREE MONTHS FROM THE "MAILING DATE" on Noted below. Failure to timely comply will result in ABANDONME THIS THREE-MONTH PERIOD IS NOT EXTENDABLE. 4 A SUBSTITUTE OATH OR DECLARATION must be submit INFORMAL PATENT APPLICATION (PTO-152) which gives the Notice of Draftsperson of Corrected Drawings (a) including changes required by the Notice of Draftsperson (b) including changes required by the attached Examiner's Paper No./Mail Date Identifying indicia such as the application number (see 37 CFR 1.6 each sheet. Replacement sheet(s) should be labeled as such in the Office of Deposition of the Of	OR REMAINS) CLOSED in this apport other appropriate communication GHTS. This application is subject to and MPEP 1308. OS filed 3/25/05 & 10/31/05. Deen received. Deen received in Application No uments have been received in this result of this communication to file a reply of this application. In this communication to file a reply of this application. In this communication to file a reply of this application. In this communication to file a reply of this application. In this communication to file a reply of this application. In this communication to file a reply of this application. In this communication to file a reply of this application. In this communication to file a reply of this application. In this communication to file a reply of this application. In this communication to file a reply of this application. In this communication to file a reply of this application. In this communication to file a reply of this application. In this communication to file a reply of this application.	polication. If not included will be mailed in due course. THIS is withdrawal from issue at the initiative inational stage application from the complying with the requirements. S AMENDMENT or NOTICE OF tion is deficient. 948) attached ffice action of the sack) of the initiative in the front (not the back) of the submitted. Note the
Attachment(s) 1. ☐ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948) 3. ☑ Information Disclosure Statements (PTO-1449 or PTO/SB/08 Paper No./Mail Date 3/25/05 & 10/31/05 4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material	6. ☐ Interview Summary (Paper No./Mail Date 3), 7. ☐ Examiner's Amendm	9

U.S. Patent and Trademark Office PTOL-37 (Rev. 7-05) Application/Control Number: 10/721,920

Art Unit: 2822

DETAILED ACTION

*** This office action is in response to communication dated March 25, 2005 and October 31, 2005. Claims 1-72 are pending.

Allowable Subject Matter

- 1. Claims 1-72 are allowed for reasons as already of record, and repeated herein.
- 2. The following is a statement of reasons for the indication of allowable subject matter:

As already of record, the references including Matthews (5,171,713), Thomas (5,00818), Farrar (5,891,797), Filipiak (5,447,887), etc., of record, alone or in combination, do not fairly anticipatively disclose each and every aspect of the claimed method, or fairly make a prima facie obvious case of the claimed method, in combination with other processing claimed limitations as recited in base claims, the inclusion of forming a silicide layer on the number of multilayer metal lines separated by a number of air gaps above a substrate; oxidizing the silicide layer (as in base claims 1,12,19), or nitriding the silicide layer (as in base claims 6 and 26), or hermetically sealing the metal lines with an oxide layer or a nitride layer on the silicide layer (as in other remaining base claims 33,36,37,39,40,43,47,56,61,65,67,68,69-72); and depositing a low dielectric constant insulator to fill a number of interstices between the number of multilayer metal lines. Farrar '797 just teaches a multiplayer copper metal lines 710,120 forming a metal line air-bridge structure covered with an insulator layer of low dielectric constant. Filipiak '887 just teaches forming a silicide layer 32 as a capping layer on the copper metal line 30, wherein the silicide layer 32 is not hermetic sealing. Matthews '713 and Thomas '818 just teach forming a number of multilayer metal lines separated by a number of air gaps above the substrate, and depositing a dielectric to fill a number of interstices.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Michael Trinh whose telephone number is (571) 272-1847. The examiner can normally be reached on M-F, 9:00 Am to 5:30 Pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Amir Zarabian can be reached on (571) 272-1852. The fax phone numbers for the organization where this application proceeding is (703) 872-9306.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-0956.

Oacs-15

Michael Trinh
Primary Examiner